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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/578,026	03/13/2007	Jozef Thomas Martinus Van Beek	EPC-019	4725
25962 7590 09/08/2009 SLATER & MATSIL, L.L.P.			EXAMINER	
17950 PRESTO	N RD, SUITE 1000		KUSUMAKAR, KAREN M	
DALLAS, TX 75252-5793			ART UNIT	PAPER NUMBER
			2829	
			MAIL DATE	DELIVERY MODE
			09/08/2009	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)
	10/578,026	VAN BEEK ET AL.
Office Action Summary	Examiner	Art Unit
	KAREN M. KUSUMAKAR	2829
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	orrespondence address
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D  - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period  - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailin earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION (36(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).
Status		
Responsive to communication(s) filed on <u>05 №</u> This action is <b>FINAL</b> . 2b) This 3) Since this application is in condition for alloward closed in accordance with the practice under №	s action is non-final. nce except for formal matters, pro	
Disposition of Claims		
4)  Claim(s) 1-8 and 12-16 is/are pending in the a 4a) Of the above claim(s) is/are withdra 5)  Claim(s) 1-7 and 12-16 is/are allowed. 6)  Claim(s) 8 is/are rejected. 7)  Claim(s) is/are objected to. 8)  Claim(s) are subject to restriction and/o	wn from consideration.	
Application Papers		
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) acc Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Example 11.	epted or b) objected to by the I drawing(s) be held in abeyance. See tion is required if the drawing(s) is obj	e 37 CFR 1.85(a). lected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	ts have been received. ts have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO/SB/08)  Paper No(s)/Mail Date	4)  Interview Summary Paper No(s)/Mail Da 5)  Notice of Informal P 6) Other:	ate

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#### **DETAILED ACTION**

# Request for Continued Examination

1. The request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e) and a submission, filed on 6/19/09 is accepted.

## Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claim 8 is rejected under 35 U.S.C. 103(a) as being unpatentable over *Kubena* et al. (US 6,580,138) in view of *Ruffner et al.* (US 5,949,071).

Kubena teaches an electronic device comprising a microelectromechanical systems (MEMS) element at a first side of a substrate (see
Abstract and Fig. 12A), the MEMS element comprising a first (contact electrode
38-2) and a second electrode (element 22-2, Fig. 12A) that is movable towards
and from the first electrode between a closed and an opened position (col. 2:3033), and that is separated from the first electrode by an air gap in its opened
position (Fig. 12A), wherein the device comprises an etch stop layer (silicon
dioxide layer 34, Fig. 12A) between the first electrode and the substrate (col.
6:46-48), the etch stop layer comprising a substantially non- conducting, fluorine

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chemistry inert material that is inert again chemical dry etching using fluorine chemistry (silicon dioxide is resistant to fluorine) and the substrate being etchable with fluorine chemistry (the substrate is silicon, and silicon is etchable with fluorine).

Kubena does not teach the etch stop layer comprises HfO<sub>2</sub>, ZrO<sub>2</sub>, or TiO<sub>2</sub>. However, Ruffner does teach the use of TiO<sub>2</sub> as an etch stop layer (col. 8:46-51). Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to use an etch stop layer comprising TiO<sub>2</sub> as taught by Ruffner so as to achieve a higher etch selectivity.

# Allowable Subject Matter

4. Claims 1-7 and 12-16 are allowed. See Office Action dated 3/5/09 for reasons for allowance.

### Conclusion

- 5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Hwang et al. (US 2003/0059720) para. [0178] and Dove et al. (US 2001/0051302) para. [0042] show the use of high-k dielectric materials, in general, and TiO<sub>2</sub>, specifically, as an etch stop layer for better etch selectivity.
- 6. Any response to this Office Action should be faxed to (571) 273-8300 or mailed to:

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Hand-Delivered responses should be brought to:

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to KAREN M. KUSUMAKAR whose telephone number is (571) 270-3520. The examiner can normally be reached on Mon - Thurs 7:30a - 5:00p EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Ha Nguyen can be reached on 571-272-1678. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic

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Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/K. M. K./ Examiner, Art Unit 2829 8/31/2009

/Ha T. Nguyen/

Supervisory Patent Examiner, Art Unit 2829